Amendments to the Specification:

Please replace the title as follows:

~~EXPOSURE APPARATUS AND METHOD FOR MANUFACTURING DEVICE~~

EXPOSURE APPARATUS AND DEVICE FABRICATION METHOD

Please replace the paragraph beginning on page 3, line 16, with the following rewritten paragraph:

An exposure apparatus of the present invention is an exposure apparatus that exposes a substrate via a liquid, including: a nozzle member having at least any one of a supply outlet that supplies ~~the~~ a liquid and a collection inlet that collects ~~the~~ a liquid; and a vibration isolating mechanism that supports the nozzle member and vibrationally isolates the nozzle member from a prescribed support member.

Please replace the paragraph beginning on page 4, line 1, with the following rewritten paragraph:

An exposure apparatus of the present invention is an exposure apparatus that exposes a substrate via a liquid, including: a nozzle member having at least any one of a supply outlet that supplies ~~the~~ a liquid and a collection inlet that collects ~~the~~ a liquid; a support member that supports the nozzle member; and an adjustment mechanism that adjusts a positional relationship between the support member and the nozzle member.

Please replace the paragraph beginning on page 4, line 12, with the following rewritten paragraph:

An exposure apparatus of the present invention is an exposure apparatus that exposes a substrate via an optical system and a liquid, including: a nozzle member supported by a

prescribed support member, and having at least any one of a supply outlet that supplies ~~the~~ a liquid and a collection inlet that collects ~~the~~ a liquid; and an adjustment mechanism that adjusts a positional relationship between the optical system and the nozzle member.

Please replace the paragraph beginning on page 4, line 24, with the following rewritten paragraph:

An exposure apparatus of the present invention is an exposure apparatus that exposes a substrate via a liquid, including: a nozzle member supported by a prescribed support member, and having at least any one of a supply outlet that supplies ~~the~~ a liquid and a collection inlet that collects ~~the~~ a liquid; a substrate stage that holds the substrate; and an adjustment mechanism that has a drive apparatus that drives the nozzle member with respect to the support member, and that adjusts a positional relationship between the substrate stage and the nozzle member.

Please replace the paragraph beginning on page 5, line 12, with the following rewritten paragraph:

An exposure apparatus according to another aspect of the present invention is an exposure apparatus that exposes a substrate via a liquid, having: a nozzle member that has at least any one of a supply outlet that supplies ~~the~~ a liquid and a collection inlet that collects ~~the~~ a liquid; in which, at least one part of the nozzle member is movable in the optical axis direction of the exposure light that exposes the substrate.

Please replace the paragraph beginning on page 13, line 25, with the following rewritten paragraph:

The ends of the X guide stage 54 in the longitudinal direction are provided with the pair of Y linear motors 51, 52 capable of moving this X guide stage 54 along with the substrate stage PST in the Y axial direction. The Y linear motors 51, 52 respectively have sliders 51B, 52B, provided at both ends of the X guide stage 54 in the longitudinal direction, and stators 51A, 52A provided corresponding to these sliders 51B, 52B. The stators 51A, ~~51B~~ 52A are supported on the base plate BP. Furthermore, the X guide stage 54 along with the substrate stage PST moves in the Y axial direction by driving the sliders 51B, 52B with respect to the stators 51A, 52A. In addition, the X guide stage 54 can also be rotated in the θZ direction by adjusting the respective drives of the Y linear motors 51, 52. Accordingly, the substrate stage PST is movable substantially integrally with the X guide stage 54 in the Y axial direction and the θZ direction by these linear motors 51, 52.

Please replace the paragraph beginning on page 17, line 6, with the following rewritten paragraph:

The nozzle member 70 is provided above the substrate P (the substrate stage PST), and includes liquid supply ports (liquid supply outlets) 12 (12A, 12B) disposed so that they oppose the surface of the substrate P. In the present embodiment, the nozzle member 70 has two liquid supply ports 12A, 12B. The liquid supply ports 12A, 12B are provided at a lower surface 70A of the nozzle member 70.

Please replace the paragraph beginning on page 17, line 15, with the following rewritten paragraph:

Furthermore, the nozzle member 70 is provided above the substrate P (the substrate stage PST), and has liquid collection ports (liquid collection inlets) 22 (22A, 22B) disposed so that they oppose the surface of the substrate P. In the present embodiment, the nozzle

member 70 has two liquid collection ports 22A, 22B. The liquid collection ports 22A, 22B are provided at the lower surface 70A of the nozzle member 70.

Please replace the paragraph beginning on page 22, line 6, with the following rewritten paragraph:

Thus, the vibration isolating mechanism 60 can drive the nozzle member ~~60~~70 by the plurality of drive apparatuses 61 - 63 in the directions (X axis, Y axis, Z axis, θX, θY and θZ directions) of the six degrees of freedom.

Please replace the paragraph beginning on page 22, line 9, with the following rewritten paragraph:

Furthermore, in the present embodiment, the same number of passive ~~drive mechanisms~~ vibration isolating mechanisms 72 (72A - 72C) and Z drive apparatuses 63 (63A - 63C) are provided. In addition, as depicted in FIG. 3, the passive ~~drive apparatuses~~ vibration isolating mechanisms 72A - 72C and the Z drive apparatuses 63A - 63C are respectively disposed mutually adjacent.

Please replace the paragraph beginning on page 22, line 13, with the following rewritten paragraph:

Furthermore, the count and placement of the X drive apparatuses 61, the Y drive apparatus 62, and the Z drive apparatuses 63 are arbitrarily settable. For example, the Z drive apparatuses 63 may be provided so that the lower surface of the flange part 70T of the nozzle member 70 and the bottom surface 7A of a recessed part ~~7T~~7H of the lower side step part 7 are coupled. Alternatively, one X drive apparatus 61 and two Y drive apparatuses 62 may be provided. In other words, the nozzle member 70 may be constituted using a plurality of drive

apparatuses 61 - 63 so that the nozzle member 70 can be driven in the directions of the six degrees of freedom.

Please replace the paragraph beginning on page 22, line 21, with the following rewritten paragraph:

In addition, the working points of the passive ~~drive mechanisms~~ vibration isolating mechanisms 72 (72A - 72C) on the nozzle member 70 and the working points of the Z drive apparatuses 63 (63A - 63C) on the nozzle member 70 are respectively coincident in the XY plain, but the corresponding working points may be set so that they are positioned on the same line (axis).

Please replace the paragraph beginning on page 25, line 12, with the following rewritten paragraph:

The count and placement of the X interferometers 81, the Y interferometer 82, and the Z interferometers 83 can be arbitrarily set. For example, the Z interferometers 83 may be provided so that they measure the distance (the relative position) between the lower surface of the flange part 70T of the nozzle member 70 and the bottom surface 7A of the recessed part ~~7T~~7H of the lower side step part 7. Alternatively, one X interferometer 81 and two Y interferometers 82 may be provided. In other words, it may be constituted so that the position of the nozzle member 70 in the directions of the six degrees of freedom can be measured using the plurality of interferometers 81 - 83.

Please replace the paragraph beginning on page 38, line 13, with the following rewritten paragraph:

Based on the measurement results of the plurality of interferometers 111 ~~103~~113, the control apparatus CONT can derive the position of the nozzle member 70 with respect to the substrate stage PST in the directions (X axis, Y axis, Z axis, θX, θY and θZ directions) of the six degrees of freedom. The control apparatus CONT adjusts the positional relationship between the substrate stage PST and the nozzle member 70 by driving the drive apparatuses 61 - 63 based on the derived position information mentioned above.